



ADDISON ENGINEERING, INC. ♦ 150 NORTECH PARKWAY ♦ SAN JOSE, CA 95134 ♦ 408-926-5000 ♦ WWW.ADDISONENGINEERING.COM

RCA Clean

Used widely in the semiconductor industry to remove organic and metallic residues.

RCA-1 - Removes organic residues

5 H₂O (DI Water)

1 NH₄OH (Ammonium Hydroxide)

1 H₂O₂ (Hydrogen Peroxide)

RCA-2 - Removes metallic residues

6 H₂O (DI Water)

1 HCl₂ (Hydrochloric Acid)

1 H₂O₂ (Hydrogen Peroxide)

Process

5 min. in RCA-1 at 70°C

5 min. in DI water rinse

5 min. in RCA-2 at 70°C

DI water rinse to 10 megohm-cm